

<b>Notice of References Cited</b>	Application/Control No. 10/790,606	Applicant(s)/Patent Under Reexamination LU, JIONG-PING	
	Examiner Long K. Tran	Art Unit 2818	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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*	B	US-6,534,871	03-2003	Maa et al.	257/769
*	C	US-6,686,274	02-2004	Shimazu et al.	438/653
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	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.